

MRS

BULLETIN

July 1992, Volume XVII, No. 7

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A Publication of the Materials Research Society



Mechanical Behavior of Thin Films

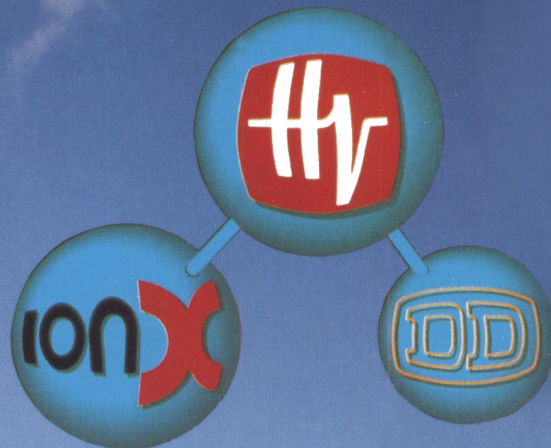


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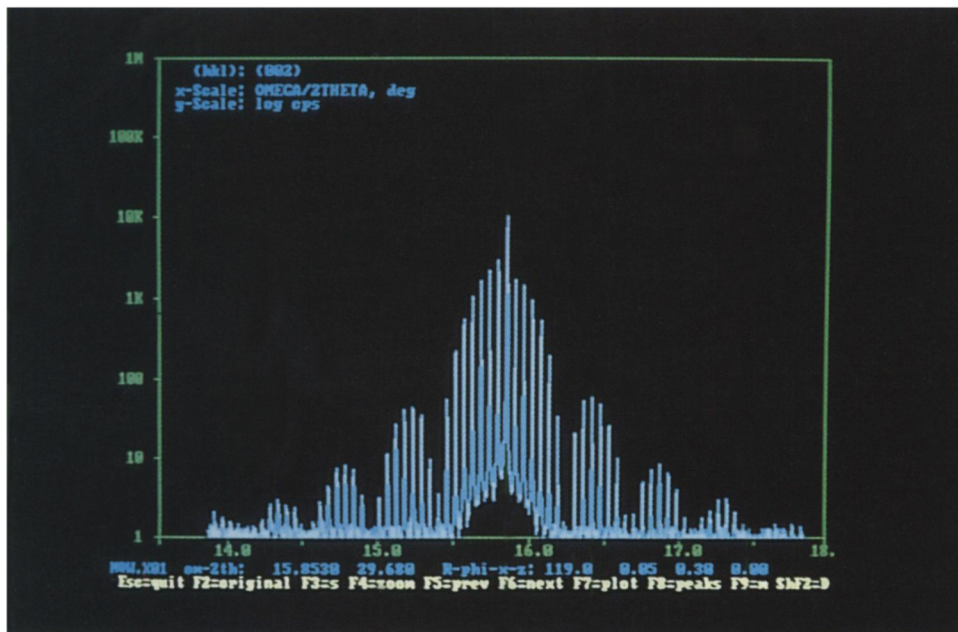
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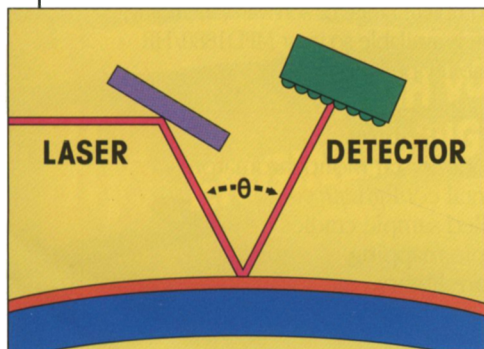
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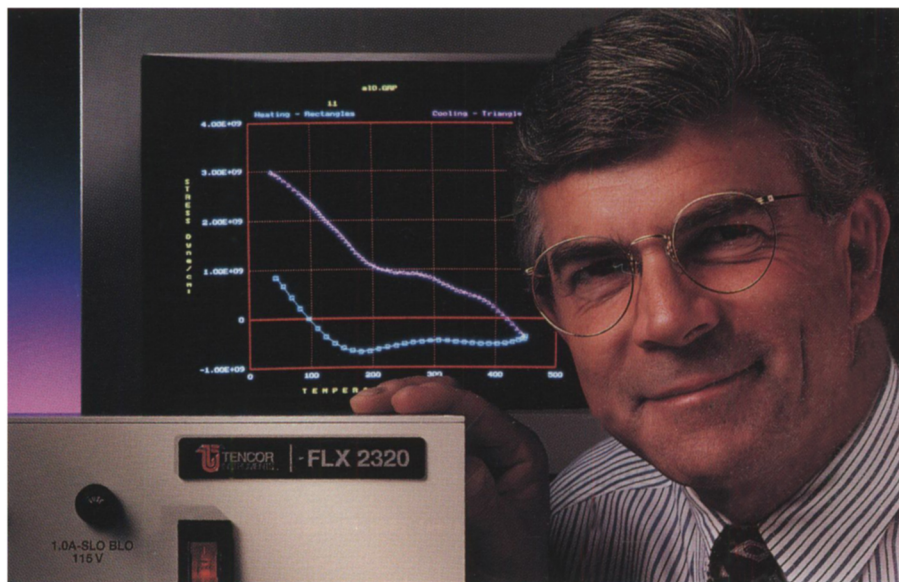
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MRS BULLETIN

July 1992

A Publication of the Materials Research Society

Volume XVII, Number 7 ISSN: 0883-7694 CODEN: MRSBEA

MECHANICAL BEHAVIOR OF THIN FILMS

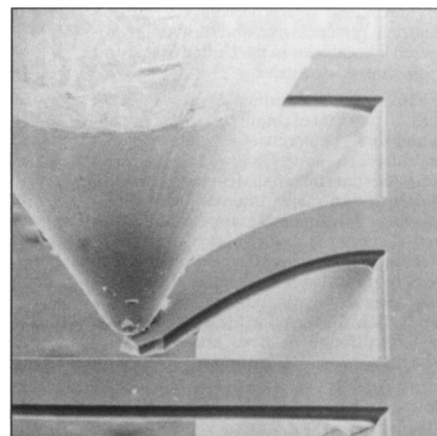
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ON THE COVER: A cantilever beam bending experiment illustrates the remarkable elastic resilience of micro-sized silicon structures. For more about this topic, see "Mechanical Characterization of Thin Films by Micromechanical Techniques" by J.-Å. Schweitz on p. 34.

About the Materials Research Society

The Materials Research Society (MRS), a nonprofit scientific association founded in 1973, promotes interdisciplinary goal-oriented basic research on materials of technological importance. Membership in the Society includes more than 10,000 scientists, engineers, and research managers from industrial, government, and university research laboratories in the United States and more than 40 countries.

The Society's interdisciplinary approach differs from that of single-discipline professional societies because it promotes information exchange across the many technical fields touching materials development. MRS sponsors two major international annual meetings encompassing approximately 50 topical symposia, and also sponsors numerous single-topic scientific meetings. The Society recognizes professional and technical excellence, conducts short courses, and fosters technical interaction in local geographic regions through Sections and University Chapters.

MRS participates in the international arena of materials research through the International Union of Materials Research Societies (IUMRS). MRS is an affiliate of the American Institute of Physics.

MRS publishes symposium proceedings, *MRS Bulletin*, *Journal of Materials Research*, and other publications related to current research activities.

MRS Bulletin (ISSN: 0883-7694) is published 12 times a year by the Materials Research Society, 9800 McKnight Road, Pittsburgh, PA 15237. Application to mail at second class rates has been approved at Pittsburgh, PA and at additional mailing offices. POSTMASTER: Send address changes to *MRS Bulletin* in care of the Materials Research Society, at the address listed; phone (412) 367-3003; Fax (412) 367-4373

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MRS Bulletin is included in Current Contents/*Physical, Chemical & Earth Sciences*[™], *Research Alert*, and the *Materials Science Citation Index*[™]. Back volumes of *MRS Bulletin* are available in 16mm microfilm, 35mm microfilm, or 105mm microfiche through University Microfilms Inc., 300 North Zeeb Road, Ann Arbor, Michigan 48106.

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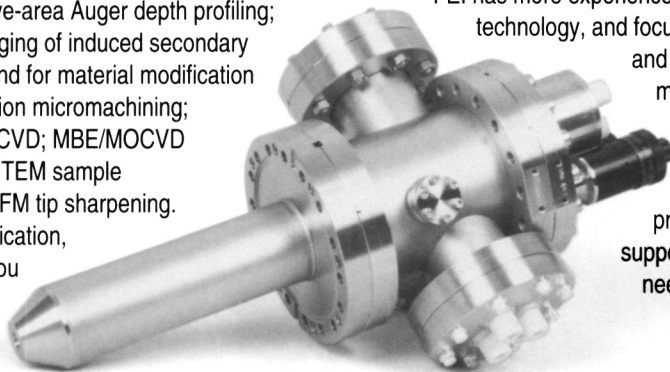
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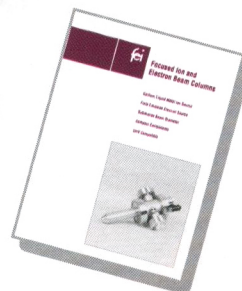
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